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List of Publications by Year in descending order

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38 papers	752 citations	623734 14 h-index	526287 27 g-index
38 all docs	38 docs citations	38 times ranked	854 citing authors

#	Article	IF	Citations
1	Challenges and solutions for post-CMP cleaning at device and interconnect levels. , 2022, , 503-532.		3
2	Suppression of Dissolution Rate via Coordination Complex in Tungsten Chemical Mechanical Planarization. Applied Sciences (Switzerland), 2022, 12, 1227.	2.5	3
3	Measurement of the force required to move ceria particles from SiO2 surfaces using lateral force microscopy. Journal of Materials Research, 2022, 37, 1789-1797.	2.6	2
4	3D trajectories and diffusion of single ceria particles near a glass surface and their removal. Journal of Materials Research, 2021, 36, 258-267.	2.6	2
5	A review on chemical and mechanical phenomena at the wafer interface during chemical mechanical planarization. Journal of Materials Research, 2021, 36, 235-257.	2.6	55
6	Direct Observation of Adsorption of Ceria Particles on the Silicon Dioxide Surfaces and Their Removal. ECS Meeting Abstracts, 2021, MA2021-01, 832-832.	0.0	0
7	Challenges and Solutions for Post-CMP Cleaning of Ceria Particles for Advanced Technology Nodes. ECS Meeting Abstracts, 2021, MA2021-01, 811-811.	0.0	0
8	Real-Time Visualization of the Cleaning of Ceria Particles from Silicon Dioxide Films Using PVA Brush Scrubbing. ECS Journal of Solid State Science and Technology, 2021, 10, 084004.	1.8	5
9	Storage Temperature Effects on the Slurry Health Parameters and SiO₂ Removal Rates during Chemical Mechanical Polishing. ECS Journal of Solid State Science and Technology, 2021, 10, 104002.	1.8	1
10	A review on chemical and mechanical phenomena at the wafer interface during chemical mechanical planarization. Journal of Materials Research, 2021, 36, 1-23.	2.6	5
11	3D trajectories and diffusion of single ceria particles near a glass surface and their removal. Journal of Materials Research, 2021, 36, 1-10.	2.6	0
12	Cleaning Solutions for Removal of â¼30 nm Ceria Particles from Proline and Citric Acid Containing Slurries Deposited on Silicon Dioxide and Silicon Nitride Surfaces. ECS Journal of Solid State Science and Technology, 2020, 9, 044013.	1.8	20
13	Trajectories, diffusion, and interactions of single ceria particles on a glass surface observed by evanescent wave microscopy. Journal of Materials Research, 2020, 35, 321-331.	2.6	8
14	Post-CMP Cleaning Solutions for the Removal of Organic Contaminants with Reduced Galvanic Corrosion at Copper/Cobalt Interface for Advanced Cu Interconnect Applications. ECS Journal of Solid State Science and Technology, 2019, 8, P379-P387.	1.8	34
15	Formation of Cobalt-BTA Complexes and Their Removal from Various Surfaces Relevant to Cobalt Interconnect Applications. ECS Journal of Solid State Science and Technology, 2019, 8, P3009-P3017.	1.8	28
16	Ammonium Persulfate and Potassium Oleate Containing Silica Dispersions for Chemical Mechanical Polishing for Cobalt Interconnect Applications. ECS Journal of Solid State Science and Technology, 2019, 8, P3001-P3008.	1.8	44
17	Environmentally-harmless polylactic acid-polyethylene glycol binder for deformable ceramic green body. Ceramics International, 2018, 44, 4220-4224.	4.8	3
18	Toward Functional 3D Architectured Platform: Advanced Approach to Anchor Functional Metal Oxide onto 3D Printed Scaffold. Advanced Engineering Materials, 2018, 20, 1700901.	3.5	4

#	Article	IF	Citations
19	Almost Complete Removal of Ceria Particles Down to 10Ânm Size from Silicon Dioxide Surfaces. ECS Journal of Solid State Science and Technology, 2018, 7, P243-P252.	1.8	58
20	Communicationâ€"Synergistic Effect of Mixed Particle Size on W CMP Process: Optimization Using Experimental Design. ECS Journal of Solid State Science and Technology, 2017, 6, P42-P44.	1.8	12
21	Synergistic protective effect of a BN-carbon separator for highly stable lithium sulfur batteries. NPG Asia Materials, 2017, 9, e375-e375.	7.9	85
22	Highly Dispersed Fe3+-Substituted Colloidal Silica Nanoparticles for Defect-Free Tungsten Chemical Mechanical Planarization. ECS Journal of Solid State Science and Technology, 2017, 6, P405-P409.	1.8	5
23	Communicationâ€"Corrosion Behavior of Tungsten Metal Gate in the Presence of Hydrogen Peroxide at Acidic Medium. ECS Journal of Solid State Science and Technology, 2017, 6, P169-P171.	1.8	7
24	Multi-objective optimization of tungsten CMP slurry for advanced semiconductor manufacturing using a response surface methodology. Materials and Design, 2017, 117, 131-138.	7.0	30
25	Communicationâ€"Reduction of Friction Force between Ceria and SiO₂for Low Dishing in STI CMP. ECS Journal of Solid State Science and Technology, 2017, 6, P752-P754.	1.8	5
26	Ce³⁺-enriched coreâ€"shell ceria nanoparticles for silicate adsorption. Journal of Materials Research, 2017, 32, 2829-2836.	2.6	20
27	Control of Tungsten Protrusion with Surface Active Agent during Tungsten Chemical Mechanical Polishing. ECS Journal of Solid State Science and Technology, 2017, 6, P822-P827.	1.8	8
28	Preparation and characterization of slurry for chemical mechanical planarization (CMP). , 2016, , 273-298.		15
29	Role of the oxidation state of cerium on the ceria surfaces for silicate adsorption. Applied Surface Science, 2016, 389, 311-315.	6.1	37
30	Size-dependent interactions of silica nanoparticles with a flat silica surface. Journal of Colloid and Interface Science, 2016, 483, 177-184.	9.4	25
31	Synergistic Ultrathin Functional Polymer-Coated Carbon Nanotube Interlayer for High Performance Lithiumâ€"Sulfur Batteries. ACS Applied Materials & Interfaces, 2016, 8, 20092-20099.	8.0	102
32	Optimizing a blend of a mixture slurry in chemical mechanical planarization for advanced semiconductor manufacturing using a posterior preference articulation approach to dual response surface optimization. Applied Stochastic Models in Business and Industry, 2016, 32, 648-659.	1.5	5
33	Two-dimensional Nafion nanoweb anion-shield for improved electrochemical performances of lithiumâ€"sulfur batteries. Journal of Materials Chemistry A, 2016, 4, 11203-11206.	10.3	35
34	Interpolymer complexes of poly(acrylic acid) and poly(ethylene glycol) for low dishing in STI CMP. Applied Surface Science, 2015, 353, 499-503.	6.1	15
35	Control of Adhesion Force Between Ceria Particles and Polishing Pad in Shallow Trench Isolation Chemical Mechanical Planarization. Journal of Nanoscience and Nanotechnology, 2014, 14, 4351-4356.	0.9	15
36	Effects of physico-chemical properties between poly(ethyleneimine) and silica abrasive on copper chemical mechanical planarization. Microelectronic Engineering, 2014, 113, 50-54.	2.4	10

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37	Role of the Surface Chemistry of Ceria Surfaces on Silicate Adsorption. ACS Applied Materials & Interfaces, 2014, 6, 7388-7394.	8.0	44
38	Chemical Mechanical Planarization-Related to Contaminants: Their Sources and Characteristics. , 0, , .		2